

METHOD AND APPARATUS FOR MEASUREMENT OF THIN FILMS AND RESIDUES ON SEMICONDUCTOR SUBSTRATES

ABSTRACT OF THE DISCLOSURE

A method of sensing properties of materials on a substrate is provided. The method includes scanning along a path defined over a surface of a substrate that can have a film. The substrate is configured to spin when present. The method includes sensing properties of the film at a plurality of points along the path and generating a map of the film using information from the plurality of points along the path. An apparatus for sensing properties of materials on a substrate is also provided.